

# Fashion Design One-Year AAS Degree Program—Art Specialization

<http://fitnyc.edu/fashiondesign>

## SCHOOL OF ART AND DESIGN

Applications accepted for fall and spring. NYSED: 00835 CIP: 50.0407

The Fashion Design one-year AAS program offers qualified students the opportunity to prepare for positions as designers, assistant designers, technical designers, or stylists. Through the application of design knowledge and experiential learning, the students develop their unique sense of aesthetics. Successful students will be able to adapt and apply their acquired knowledge to the evolving fashion industry, related design fields, and other creative careers. Curriculum below is for the entering class of fall 2026.

Semester 1		Credits
MAJOR AREA	FD 113 - Apparel Design: Structured Silhouettes	4
	FD 114 - Apparel Design: Soft Silhouettes	3
	FD 135 - Materials and Construction (for 1-Year AAS)	3
	FF 113 - Fashion Art and Design (for One-Year AAS)	5
	FF 115 - Digital Fashion Design Studio I (for One-Year AAS)	2
RELATED AREA	FA 105 - Life Drawing *	1.5
Semester 2		Credits
MAJOR AREA	FD 242 - Digital Fashion Design Studio II	2
	FD 243 - Apparel Design Studio - Patternmaking	3
	FF 213 - Model Visualization Techniques	1
	FF 244 - Design Collections: Visual Solutions	2
	FF 291 - Fashion Portfolio Collection	2
RELATED AREA	TS 131 - Textile Principles for the Fashion Designer	3
ELECTIVE(S)	Choice - General Elective(s)	1
TOTAL CREDIT REQUIREMENTS		
	ELECTIVE(S)	1
	MAJOR AREA	27
	RELATED AREA	4.5
	<b>Total Credits:</b>	<b>32.5</b>

**\*Fall 2026 Requirements:** See below.

### Related Area Elective(s): 1.5 credits (minimum)

FA 105 or CHOICE of another Fine Arts course

### General Education Art & Design: 24 credits

One year AAS degree programs include completion of at least 30 transferable credits from an accredited college with a minimum of 24 liberal arts credits equivalent to FIT's General Education requirements. Six (6) additional transferable elective credits are required for 30 transferable credits total.

- 6 credits in college-level written and oral English communication (3 credits each in SUNY GE: COMO and COMW or a 3 credit a combination (SUNY GE: COMO and COMW) course plus additional 3 credits in English (taken in the U.S. or in a country in which English is an official language);
- 3 credits in college-level mathematics above basic algebra
- 3 credits in physical science, biology, or life science (SUNY GE: NSCI).
- 3 credits in diversity studies, specifically the historical and social factors related to equity, inclusion and social justice (SUNY GE: DVRS)
- 9 additional credits as follows:
  - 6 credits of Art History
  - 3 credits from one of the remaining SUNY GE Areas:
    - The Arts (SUNY GE ARTS)
    - World History and Global Awareness (SUNY GE: GLBL)

- Humanities (SUNY GE: HUMN)
- Social Sciences (SUNY GE: SOCS)
- U.S. History and Civic Engagement (SUNY GE: USCV)
- World Languages (SUNY GE: WLNG)

Students who successfully complete the Fashion Design AAS program will be able to:

1. Create garments that reflect creativity and innovation through the use of foundational techniques achieved through shape, color, silhouette, proportion and fabrication.
2. Adapt and develop artistic abilities to form original fashion designs with understanding of diverse fashion proportions, utilizing hand and digital rendering techniques.
3. Effectively use appropriate, innovative technologies to conceptualize, create, produce and communicate fashion design and related concepts.
4. Develop an understanding of ethical and sustainable principles in fashion design considering environmental, social, economic, and political impacts of climate change.
5. Recognize and apply foundational concepts of diversity, equity and inclusion in the fashion design development process that honor communities and people who have been marginalized and excluded from the dominant fashion discourse.
6. Utilize information and communication technologies to research, evaluate, create, and communicate information as it relates to fashion design concepts at a foundational level.